PATENT 1752-0147P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:

FUJIYAMA, Takeshi et al Conf.:

Int'l. Appl. No.:

PCT/JP00/01955

Appl. No.:

NEW

Group:

Filed:

September 28, 2001 Examiner:

For:

SILICONE RESINS AND PHOTOSENSITIVE RESIN COMPOSITIONS CONTAINING THE

SAME

PRELIMINARY AMENDMENT

BOX PATENT APPLICATION

Assistant Commissioner for Patents Washington, DC 20231

September 28, 2001

Sir:

The following Preliminary Amendments and Remarks are respectfully submitted in connection with the above-identified application.

IN THE SPECIFICATION:

Before line 1, insert This application is the national phase under 35 U.S.C. § 371 of PCT International Application No. PCT/JP00/01955 which has an International filing date of March 29, 2000, which designated the United States of America.

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